

IN THE CLAIMS

1. - 3. (Canceled)

4. (Currently Amended) A magnetic thin film head comprising:

a write head element; and

a read head element including a sensor film;

wherein a ferromagnetic film having a soft magnetic characteristic and a magnetic shield function is provided ~~formed of NiFe permalloy material by electroplating in the vicinity of said a sensor film arranged as said read head element,~~

wherein said ferromagnetic film comprises NiFe permalloy material and is formed by an electroplating method,

wherein in a first region of said ferromagnetic film which exceeds a film thickness of exceeding 1.0 μ m from an initial formed layer, in said ferromagnetic film formed of NiFe permalloy material has an Ni content accuracy isof ± 0.1 wt%, and

wherein in a second region of said ferromagnetic film where a film thickness isof 1.0 μ m or less from said

~~initial formed layer, in said ferromagnetic film formed of NiFe permalloy material has an Ni content accuracy is of ± 0.3 wt%.~~

5. - 9 (Canceled)

10. (Currently Amended) A magnetic disk apparatus having a magnetic thin film head comprising:

a magnetic disk;

a magnetic disk driving unit;

aA magnetic thin film head comprising a write head element, and a read head element; and

a magnetic head driving unit,

wherein a ferromagnetic film having a soft magnetic characteristic and a magnetic shield function is formed of NiFe permalloy material by electroplating in the vicinity of a sensor film arranged as said read head element,

wherein in a first region of said ferromagnetic film in which a film thickness exceedsing 1.0 μm from an initial formed layer, in said ferromagnetic film formed of NiFe

~~permalloy material has an Ni content accuracy~~ is of ± 0.1 wt%,
and

wherein in a second region of said ferromagnetic
film where a film thickness is of 1.0 μm or less, ~~in said~~
~~ferromagnetic film formed of NiFe permalloy material has an Ni~~
content accuracy is of ± 0.3 wt%.

11. (New) The magnetic thin film head according to claim
4, wherein Ni in composition of said ferromagnetic film is
80.8 wt% to 82.0 wt%.

12. (New) The magnetic thin film head according to claim
4, wherein when said ferromagnetic film is formed, a current
density used for the electroplating changes.